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(54) RESIST MATERIAL AND RESIST PATTERN FORMING METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a chemical amplification type resist material having high sensitivity of $\leq 5\text{mJ}/\text{cm}^2$ required by ArF lithography and capable of ensuring stable patternability.

SOLUTION: This resist material contains an acid sensitive compd. and an acid generating agent which generates an acid when exposed with radiation. The acid sensitive compd. contains structural units each having a protected alkali-soluble group contg. a part contg. an alicyclic hydrocarbon group with $-\text{CH}_2-\text{R}$ (R is methyl, ethyl, propyl or isopropyl) bonded to C of the hydrocarbon group and the alkali-soluble group is released by the generated acid and makes the acid sensitive compd. alkali-soluble.

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